

# Powering Plasma Processes with Precision & Reliability

Modern plasma processes demand unmatched power stability, fine frequency control, and long-term reliability, areas where traditional magnetron systems fall short.

Our solid-state microwave power platform delivers clean, stable RF power up to 850W at 2.45 GHz, enabling consistent plasma performance in front-end and back-end wafer processing.

## Proven Advantages



### Uniform Plasma Profiles

Fine power & frequency tuning enhances repeatability



### Lower Tool Downtime

Solid-state architecture requires minimal maintenance



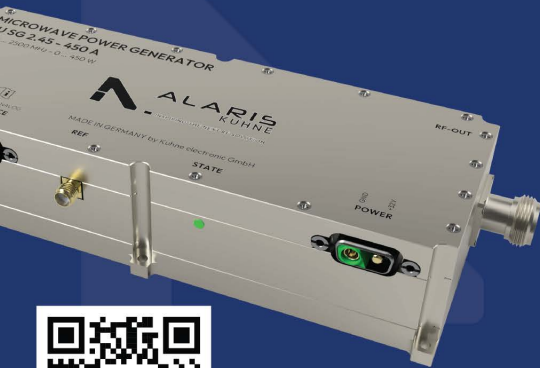
### Seamless Integration

Compact, controllable, and easy to retrofit into existing tools



## Ideal applications

- Plasma Etch (Dry, RIE)**  
 Delivers stable RF power for precise anisotropic etching and uniform critical dimension control.
- PECVD / ALD Deposition Tools**  
 Enables consistent plasma excitation for high-quality thin film deposition at low temperatures.
- Post-Etch Cleaning, Photoresist Stripping**  
 Supports residue removal and surface conditioning with controllable plasma energy profiles.
- Back-End Packaging & Substrate Treatment**  
 Improves adhesion, surface activation, and contamination control in advanced packaging processes.



## KU SG 2.45-450 A

Microwave Power Generator

- ✓ Suitable for integration into plasma chambers
- ✓ Enables real-time power ramping or feedback control (via host system)
- ✓ Operates as a standalone generator or part of a power-combined system

Frequency range	2400 ... 2500 MHz
Output power	0 ... 450 W
Power steps	1 W
Frequency steps	100 kHz (10 kHz optional)
Output connector	N-female, 50 Ω
Control input	Serial Interface, 3.3 V UART interface Analog interface 0 V ... 10 V External I2C bus extensions
Supply Voltage	32 V
Current consumption	max. 26 A @ 450 W
Dimensions	180 mm x 65 mm x 40 mm
Weight	typ. 1500 g



## KU DIV 2.45-N-716

Power Combiner Kit 850 W

- ✓ Must be used with matched KU SG units
- ✓ Ensures phase-locked output and thermal balance
- ✓ Critical for maintaining plasma uniformity in high-power systems

Frequency Range	2400 - 2500 MHz
Output power	2 - 800 W
Power Steps	2 W
Frequency Step	1 MHz
Output Connector	7/16 - Female, 50 Ω
Input Connector	2x N-Plug Male
Supply Voltage	10-36 VDC
Current Consumption	max. 100 mA
Dimensions	110 mm x 110 mm x 44 mm
Weight	typ. 1150 g



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